Amendments to the Claims

This listing of claims will replace all prior versions, and listings, of claims in the application:

- 1. (currently amended) A chemical vapor deposition apparatus comprising: a chamber having an inner space and <u>top</u>, <u>bottom</u>, <u>and</u> side wall;
- a susceptor disposed in the chamber and supporting a substrate;

a diffuser partitioning the inner space of the chamber into first and second partitions and having an extension extended out from a boundary, wherein the extension of the diffuser is exposed to the inner space of the chamber; and

an insulating frame disposed between the <u>side wall of the</u> chamber and the diffuser, said insulating frame being disposed on an upper side of the extension of the diffuser and extending to <u>and contacting</u> the side wall of the chamber.

- 2. (original) The apparatus of claim 1, wherein the extension of the diffuser has an "L" shape.
- 3. (original) The apparatus of claim 1, wherein the diffuser comprises Al or stainless steel.
- 4. (original) The apparatus of claim 1, wherein the insulating frame comprises ceramic.
 - 5. (original) The apparatus of claim 1, wherein the substrate comprises glass.
- 6. (original) The apparatus of claim 1, wherein the substrate is prepared for a liquid crystal display.
- 7. (original) The apparatus of claim 1, further comprising a blocking member for mixing and spreading the gas from the gas feed member before the gas passes through the holes of the diffuser.

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- 8. (original) The apparatus of claim 1, wherein the diffuser is electrically powered and the susceptor is electrically grounded.
 - 9. (previously presented) The apparatus of claim 1, further comprising: a gas feed member for supplying a gas into the chamber.
- 10. (previously presented) The apparatus of claim 1, wherein the extension overlaps a surface of the insulating frame facing the susceptor.
 - 11. (currently amended) A chemical vapor deposition apparatus comprising: a chamber having an inner space and <u>top</u>, <u>bottom</u>, <u>and</u> side wall; a susceptor disposed in the chamber and supporting a substrate;
- a diffuser partitioning the inner space of the chamber into first and second partitions and having an extension of an "L" shape extended out from a boundary, wherein the extension of the diffuser is exposed to the inner space of the chamber; and

an insulating frame disposed between the <u>side wall of the</u> chamber and the diffuser, said insulating frame being disposed on an upper side of the extension of the diffuser and extending to <u>and contacting</u> the side wall of the chamber.

12. (previously presented) The apparatus of claim 11, wherein the extension overlaps a surface of the insulating frame facing the susceptor.

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